ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /J.V./

PTO:SB/08a (06-03)
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## COMPLETE IF KNOWN 10/533.822 Application Number Filing Date August 31, 2005 INFORMATION DISCLOSURE First Named Inventor Mino Green STATEMENT BY APPLICANT(S) Art Unit 2815 (Use as many sheets as necessary) Examiner Name Jami M. Valentine Sheet 1 of 3 Attorney Docket No. KSTR 2 00004 U.S. PATENT DOCUMENTS Examiner Cite Document No. **Publication Date** Name of Patentee or Number-Kind Code (# known) Initials\* No. MM-DD-YYYY Applicant of Cited Document AA US-FOREIGN PATENT DOCUMENTS

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